

# AME P5000 Chamber A

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## Facts

The AME P5000 is a multi-chamber tool set up for a variety of processes

- Chamber A - PECVD of TEOS Silicon Dioxide
- TEOS is heated and brought into the chamber where it is subjected to an RF plasma and a heated chamber at 300 to 390C
- No gold or copper coatings allowed.
- Other Chambers
  - AME P5000 Chamber B - PECVD of Silicon Nitride / Amorphous Silicon
  - AME P5000 Chamber C - RIE of Silicon Dioxide

## Personnel

- Tool Engineer - John Nash
- Process Engineer - Sean O'Brien

## Manuals & Users

- P5000 Manual
- P5000 Certification Checklist